# Switched Capacitor DC-DC in FE-I4

Dario Gnani<sup>1</sup> (design), Yunpeng Lu<sup>2</sup> (measurement and talk), Weiguo Lu<sup>2</sup> (simulation) 1-Lawrence Berkeley National Laboratory 2-Institute of High Energy Physics, Beijing

March 8th, 2011

### **FE-I4** Introduction

- Designed in a 130nm feature size bulk silicon process.
  - Chip size:  $2cm \times 1.9cm$
  - Pixel array: 80col×336row (26,880 pixels)
  - Pixel size:  $250 \text{um} \times 50 \text{um}$
  - For each pixel: free running CSA + shaping + discriminator
  - Sophisticated digital logic porcessing "firing time" and "time over threshold(TOT)" of each pixel, and transmitting data out of the chip via a pair of 160Mb/s differential signals.

### Power Options for FE-I4

- Basically the power rail inside FE-I4 are devided into 4 groups and attached to seperate pads:
  - VDDD1/GNGD1, VDDD2/GNDD2, VDDA1/GNDA1, VDDA2/GNDA2
  - In addition dedicated power nets for PLL, EFUSE and T3 isolation as well.
- 3 isolated power modules in the chip.
  - Two linear-shunt LDOs(ShuLDO)-> Laura's talk.
  - One switched capacitor DC-DC converter-> this talk.
  - Neither is hard-wired inside the chip. Thus Wire connections outside the chip needed.



(Ground connections not shown)

### Power Modules in FE-I4 Layout



### DC-DC configuration in FE-I4



- CLOLK is provided from outside the chip. This clock also serves as auxiliary clock for the chip.
- Ceramic capacitors used for the test. Cpump is mounted on the board as close to the chip as possible.
- DCDC\_OUT and ShuLDO1\_IN are connected in the chip and share the same pad.
- As a "devide-by-two" converter, ideally: lout=2lin & Vout=Vin/2.

### **DC-DC Schematic Diagram**

- Non-overpapping Clock generator:
  - generates 3 internal clock signals from CLK\_IN
  - the same frequency but different phase.
- Charge pump:
  - consists of 4 transistors working as switches
  - manipulates the pump capacitor under control of clock signals.



### Non-overlapping clocks

5ns gap between CLK\_BOT1 and CLK\_BOT2 to eliminate adverse ٠ discharging.



### **Testing Results**

### Efficiency vs Clock frequency

#### Vin=3.3V, Rload=5Ω



- Simulation result shows Vefficiency around 90%, while the test result shows Vefficiency of about 84%.
- Just take 1MHz as the optimal frequency for the following test.

### **Ripple Voltage**

- Observed ripple voltage was much larger(7mV) than the value predicted by simulation(<1mV).</li>
- Its amplitude depended on load current(as shown in pictures below).
- We can't regenerate comparable ripple voltage by simulation. Still can't understand it by now.



### Noise in Threshold Scan



### Effect of running DC-DC standalone



• Running DC-DC but not using it to power the chip.

- Noise depends on DC-DC current.
- Seems like that DC-DC is not well isolated from the rest of the chip as expected.
- To investgate this problem, we made a test shown on next page.



## An attempt to inject switching current via DC-DC\_T3 isolation well

- DC-DC module sits in a T3 isolation well.
  - which is connected to DC-DC\_in.
  - expected to be isolated from the rest of the chip by this way.
- Injecting switching current into the T3 isolation well, to see if noise from threshold scan increased.
- But it doesn't work by far. Two alleged reasons:
  - The current(tens of mA) from the pulser is not big enough.
  - The capacitance between T3 well and substrate smoothed the little switching current.



### Follow-up



- 1. To find out where does the noise come from?
  - Put more efforts into the trial of switching current injection.
- 2. To put the pump capacitor on the bonding pads
  - smallest package available: "0201";
  - not sure it will work or not since not clear where the noise comes from.
  - should increase operating frequency--minimum of output resistance at higher frequency due to no wire bonds.
- 3. To make a board to test the irradiated chips.
  - 3 chips irradiated last Dec. and under test now.
  - But no wire bonding for DC-DC can be made on the boards.
  - Plan to make a small board sitting on top of chip. DC-DC will be wire bonded to this board and further attached to wires for test.

• Thanks for paying attention!

### **Backup Slides**

### Power Requirments in FE-I4

- 2.2nm gate oxide for all transistors(except for DC-DC converter and EFUSE programming circuitry).
- Thickest gate oxide in the process(5.2nm) used for DC-DC converter and EFUSE programming circuitry.
- The voltage ratings are conservatively estimated according to the gate oxide thickness, area, lifetime, operation temperature, and expected failure rate.
  - 1cm<sup>2</sup> gate area is rated for 1.6V with a 1ppm failure rate after 100KPOH at temperature of 125 °C.
  - The benifits from low operation temperature are not included.

		Internal Nodes	Linear Regulators	DC-DC Converter	Units
	Min. operating voltage	1.20	1.30	2.20	V
Voltage rating and current consumption	Max. operating voltage	1.50	1.65	3.40	V
	Nominal operating current	0.60	0.60	0.31	А
	Max. current at max. voltage	0.90	0.90	0.46	А
	Peak transients allowed	1.75	2.00	4.0	V
	Max. voltage at power supply <sup>1</sup>	2.10	2.50	4.73	V
	Derived R/T drop allowed in cables	0.60	0.85	1.33	V

1: The chip will see this voltage minus the cable voltage drop. This limit is chosen under the worst case assumption that a zero voltage drop in the cables can occur.

### Switched Capacitor DC-DC

- Merits of switching capacitor DC-DC:
  - converting "high volatege low current"(good for power cables) to "low voltage high current"(required by frontend electronics);
  - using capacitors for energy storage benifits from the the industrial trend of high capacity small shape capacitors( and therefore decreasing mass).
- Pending questions:
  - Noise imposed upon the analog part when integrated into the same chip.
  - Power efficiency degraded by irradiation, about 10% observed on a prototype.



